



# SRF thin films @ CERN

TE/VSC/SCC

Alban Sublet

23.06.2015 - CERN-LNL-STFC collaboration kickoff meeting

# Technical challenges

→ “Thin films & new ideas for SRF” workshop LNL’14

Miguel:

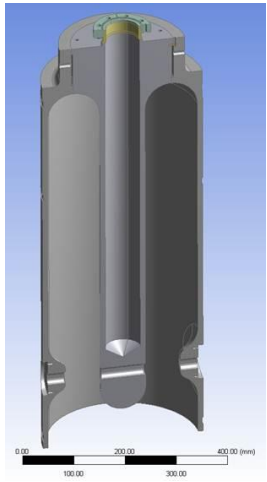
- 2018 end of run 2, start of LS2
  - run 2 physics results will define what’s needed for the future
- Cavities: bulk Nb not in-line with optimization, cost, raw material availability, need alternative for large scale projects (FCC)
  - **THIN FILM technology must be mature for 2018**
  - **2.5 years** to get to this level: get closer to bulk Nb RF-properties (Q0 + high accelerating gradients)

Erk:

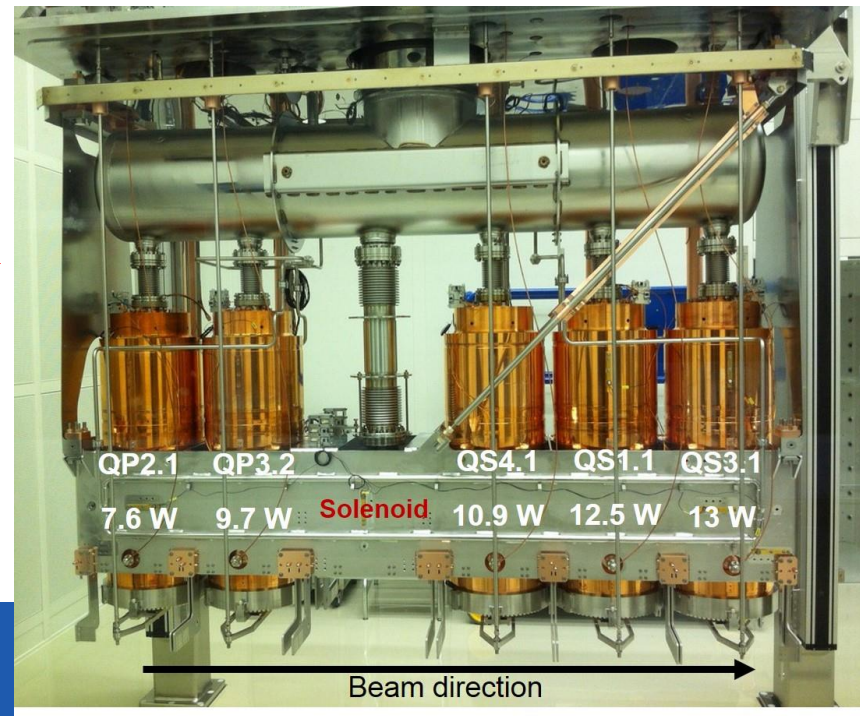
- FCC: “The design study shall be organised on a world-wide international collaboration basis under the auspices of the European Committee for Future Accelerators (ECFA) and shall be available in time for the next update of the European Strategy for Particle Physics, foreseen by 2018.”
  - **Must start studying now to be ready for 2035/2040**

# SRF thin films production activities I/II

- HIE-ISOLDE QWR 100 MHz
  - 1 test cavity with sample holder + QPR sample
  - 20 “high- $\beta$ ” cavities (phase 1 + 2) → on going
  - 12 “low- $\beta$ ” cavities (phase 3) → to be approved

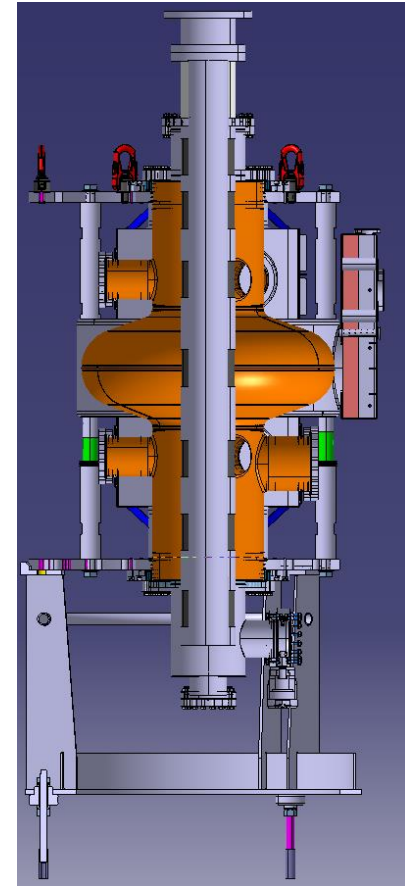
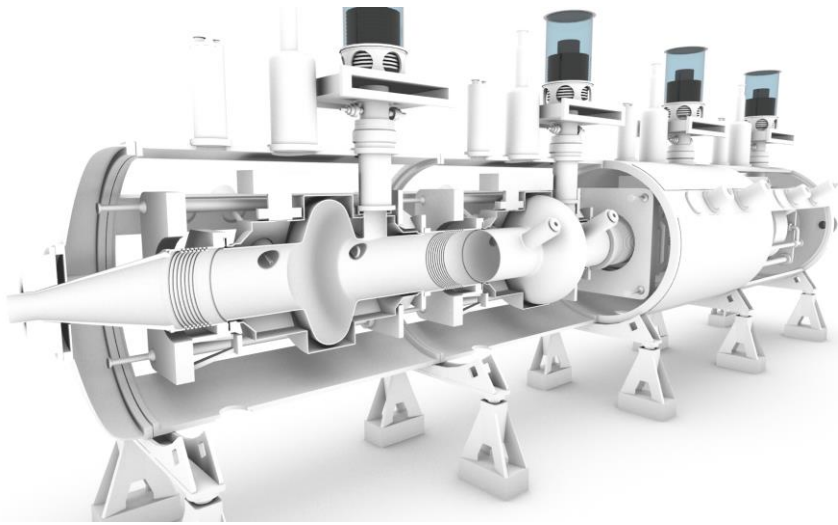


- First cryomodule under commissioning →
- Coating of cavities for second cryomodule on the way
- R&D continuing



# SRF thin films production activities II/II

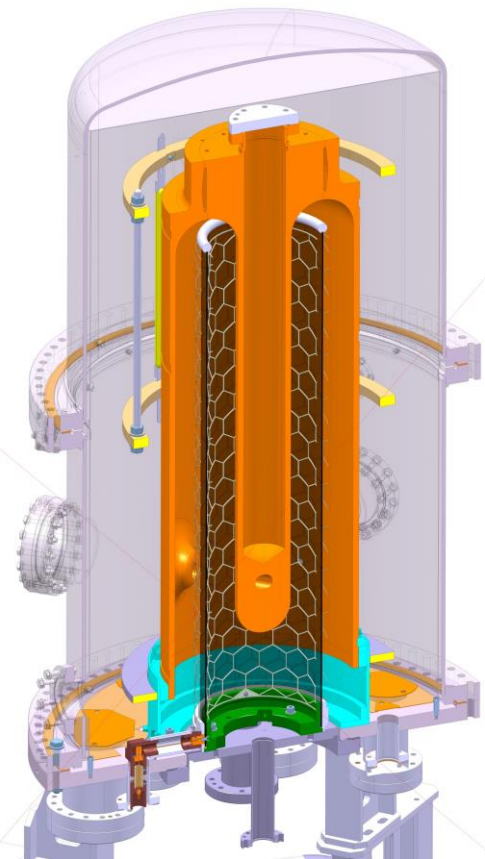
- LHC single cell 400 MHz spare cavities
  - Test tube to assess coating setup
  - 2 prototypes → fabrication on going
  - 1 full cryomodule + spares



# SRF thin films R&D: drivers I/II

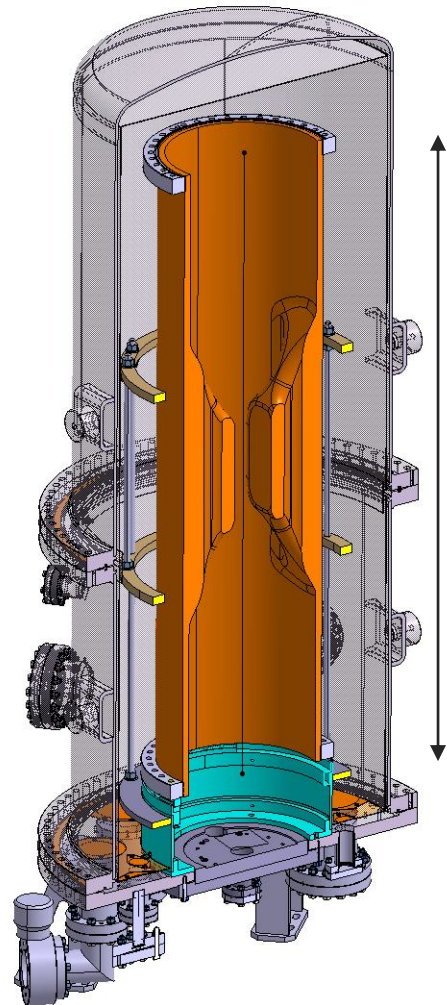
- HIE-ISOLDE high/low- $\beta$  (100 MHz)
- HL-LHC Crab Nb/Cu (400 MHz)
- LHC upgrade/ERL/FCC (800 MHz)
- FCC (400/800 MHz)

# SRF thin films R&D: drivers II/II



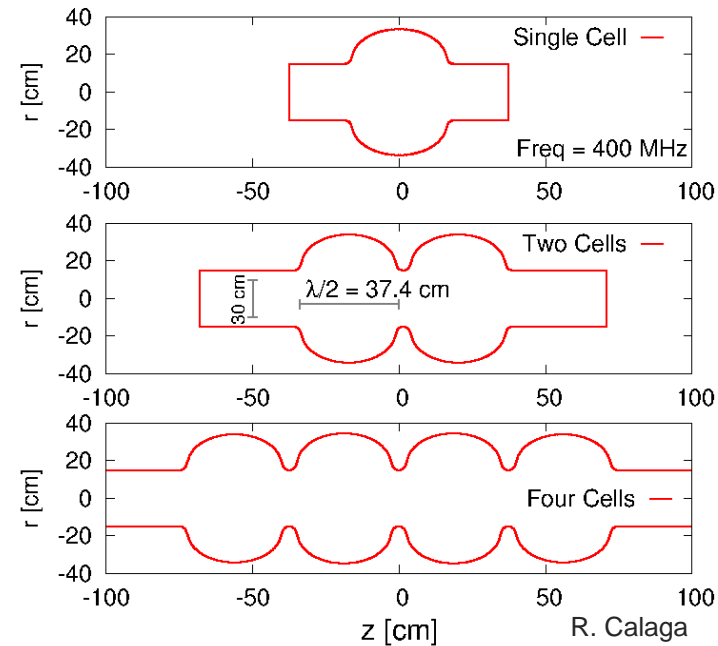
0.9 m

QWR (HIE-ISOLDE)



1.2 m

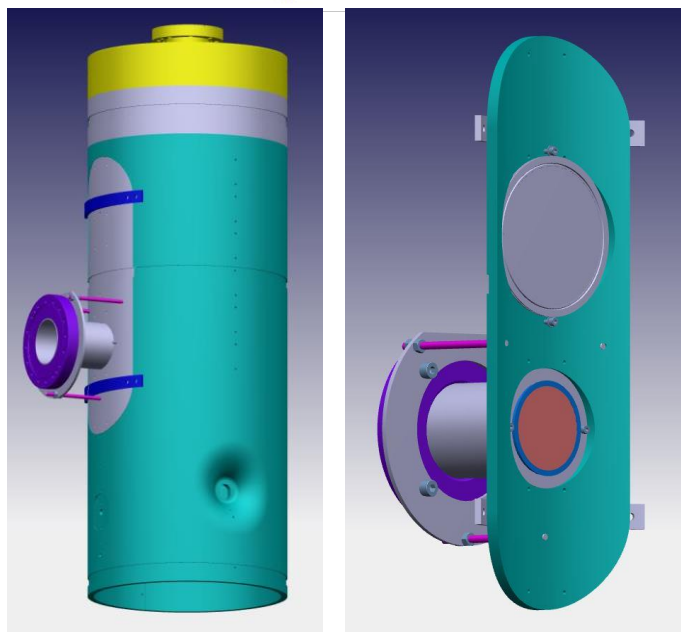
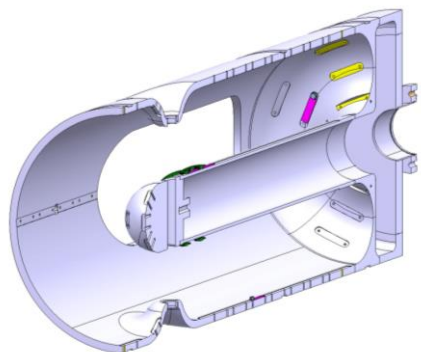
WOW Crab Nb/Cu (HL-LHC)



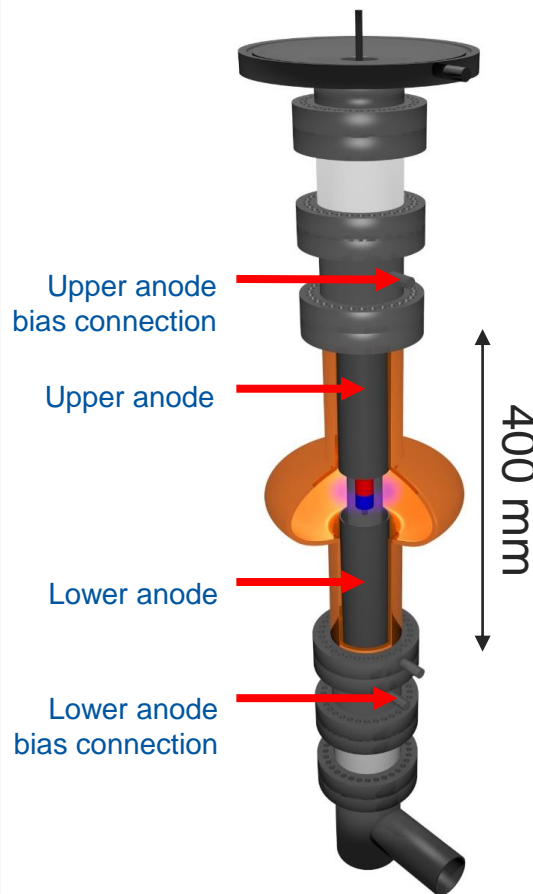
elliptical x-cell(s) (FCC)



# SRF thin films R&D: test substrates



Q4 sample cavity (HIE-ISOLDE)



elliptical 1.3 GHz



126 mm

Orsay Cu-disk



75 mm

QPR-sample



30 mm

Si-wafer/quartz/Cu coupons



# SRF thin films R&D: functionality characterization

## Basic studies:

- RRR on quartz sample → CERN
- Point Contact Tunneling (PCT) → ANL
- Muon Spin rotation ( $\mu$ -SR) → PSI/TRIUMF
- Third harmonic magnetometer → Saclay

## RF characterization:

- TE011 test cavity for Cu-disk → Orsay
- RF Quadrupole Resonator test → CERN
- RF test on 1.3 GHz cavity (cryolab) → CERN
- RF test on cavities (SM18) → CERN

# SRF thin films R&D: topics

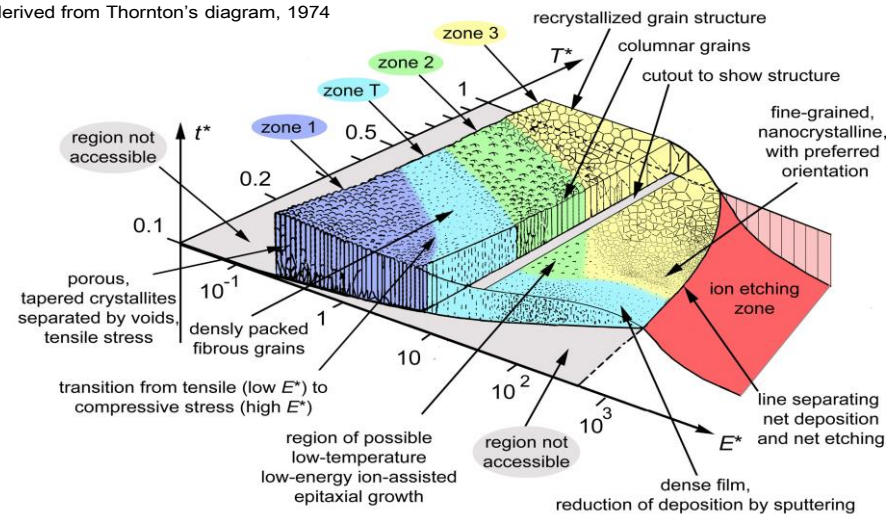
- Coating technics
- SC Material
- Material/thin film analysis
- Plasma diagnostics and plasma simulation

# SRF thin films R&D: coating technics

- DC bias diode sputtering, production level
- DC magnetron Sputtering, production level
- HiPIMS (+bias), development level

- Cathode design/shape
- Biasing, grid design
- Heat treatment
- substrate temperature
- Nitrogen treatments

derived from Thornton's diagram, 1974



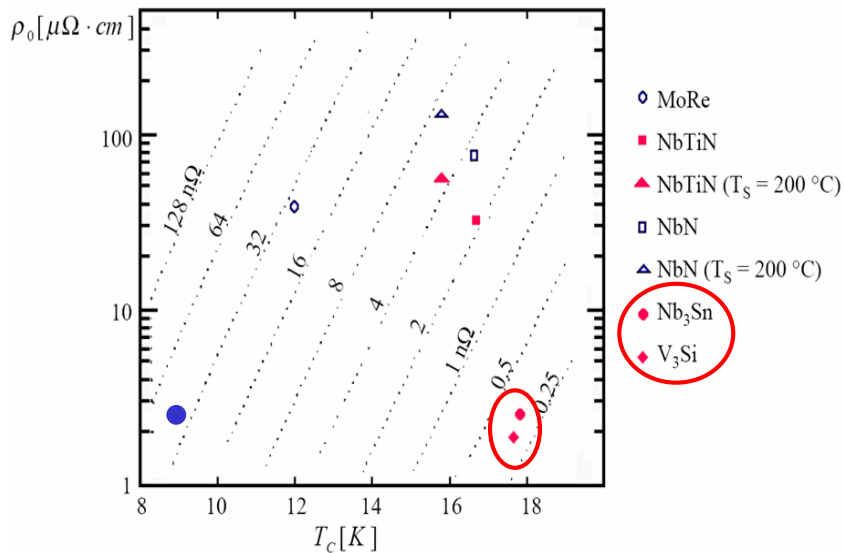
© Andre Anders, 2010

A. Anders, Thin Solid Films 518, 4087 (2010).

# SRF thin films R&D: SC material

→ Niobium

→ A15 compounds: Nb<sub>3</sub>Sn (and V<sub>3</sub>Si)



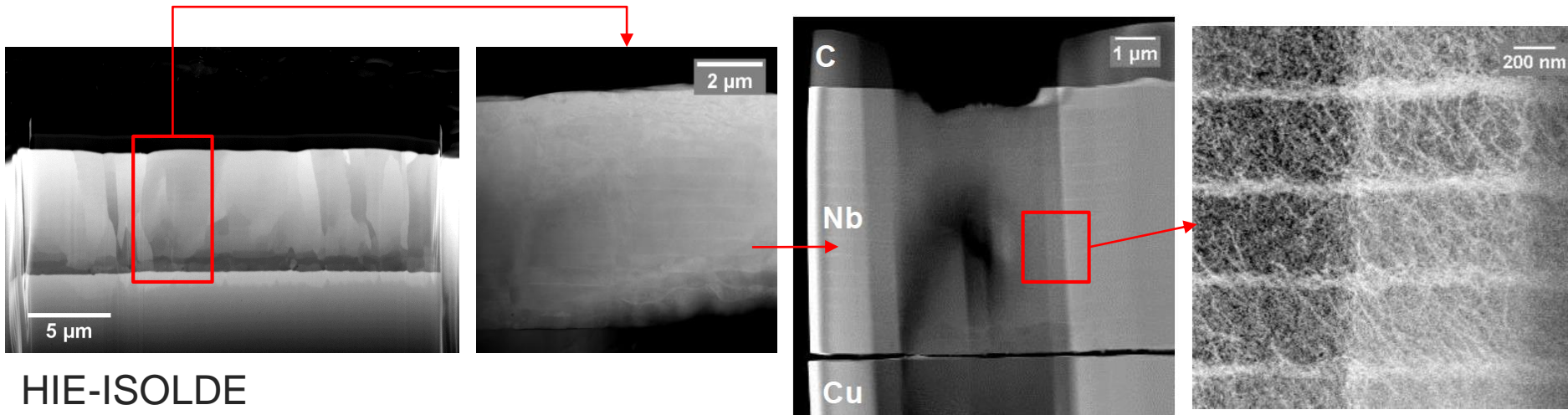
BCS surface resistance at 4.2 K  
and 500 MHz for films (● Nb ~ 45 n $\Omega$ )



Planar magnetron Nb<sub>3</sub>Sn target sputtering

# SRF thin films R&D: material/thin film analysis

- XRF, XPS, XRD (CERN), SIMS, ...
- SEM/EDS – FIB/SEM, STEM/TEM (CERN/EPFL)

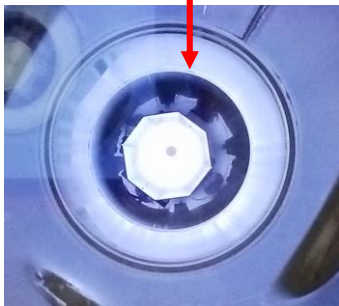


HIE-ISOLDE  
Q4 sample from middle antenna  
Nb/Cu, 14 runs coating

Courtesy B. Bartova and EPFL-CIME

# SRF thin films R&D topics: plasma diagnostics

## Plasma test bench



Bottom view of plasma

- current/voltage probes
- Retarding Field Analyzer (RFA)
- Quartz balance
- OES
- Langmuir probe

UHV vacuum chamber

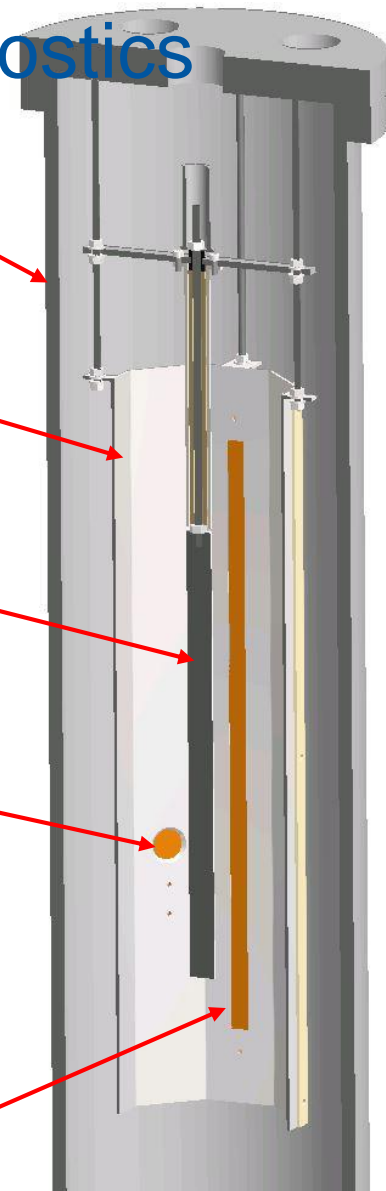
anode tube (+bias)

Nb cathode

- DC bias diode
- DCMS
- (HIPIMS)

diagnostic port:  
RFA, Qz-balance

Cu strip for  
thickness profile  
400 mm height





# SRF thin films R&D: plasma simulation

## DSMC/PIC-MC code

- $P = 0.32$  mbar (diode discharge)
  - Constant wall temperature
  - Initial charged particles density =  $10^{13}$   $\text{m}^{-3}$
  - Power = 10 W
  - Maximum voltage = 1000 V
- benchmarking with plasma test bench

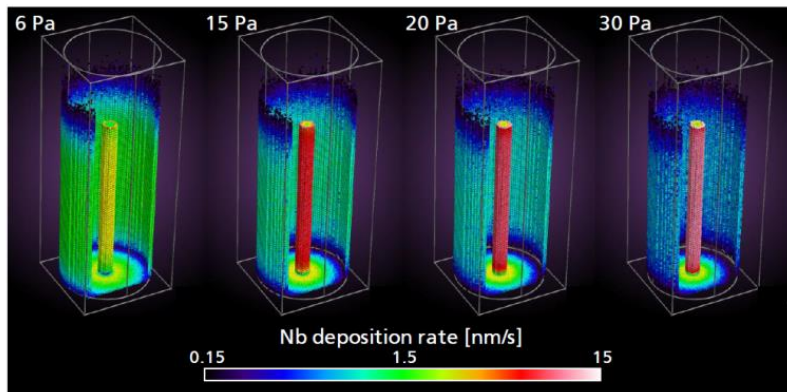
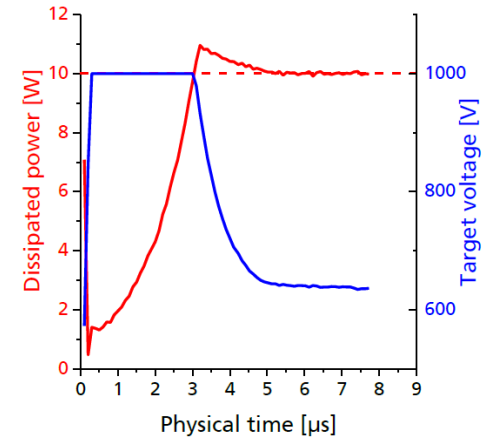
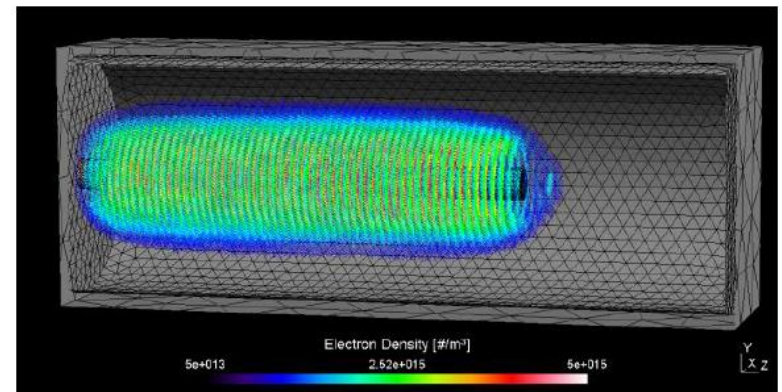


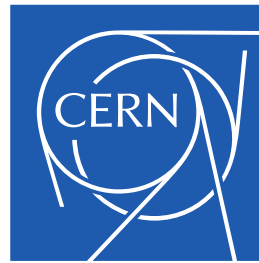
Figure 2: Simulated deposition rate on tube surface and re-deposition on target after 30 ms for different total pressures.



a) Electron density (scaled view) [ $1/\text{m}^3$ ]

Thank you for your attention





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